

Second-Pass Processing Results of AES6 & AES9

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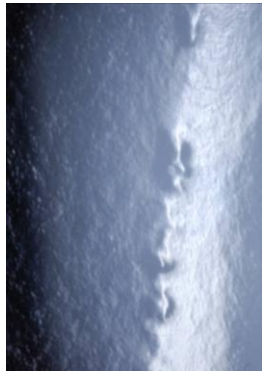
AES9 Second-Pass Processing

2nd pass processing:

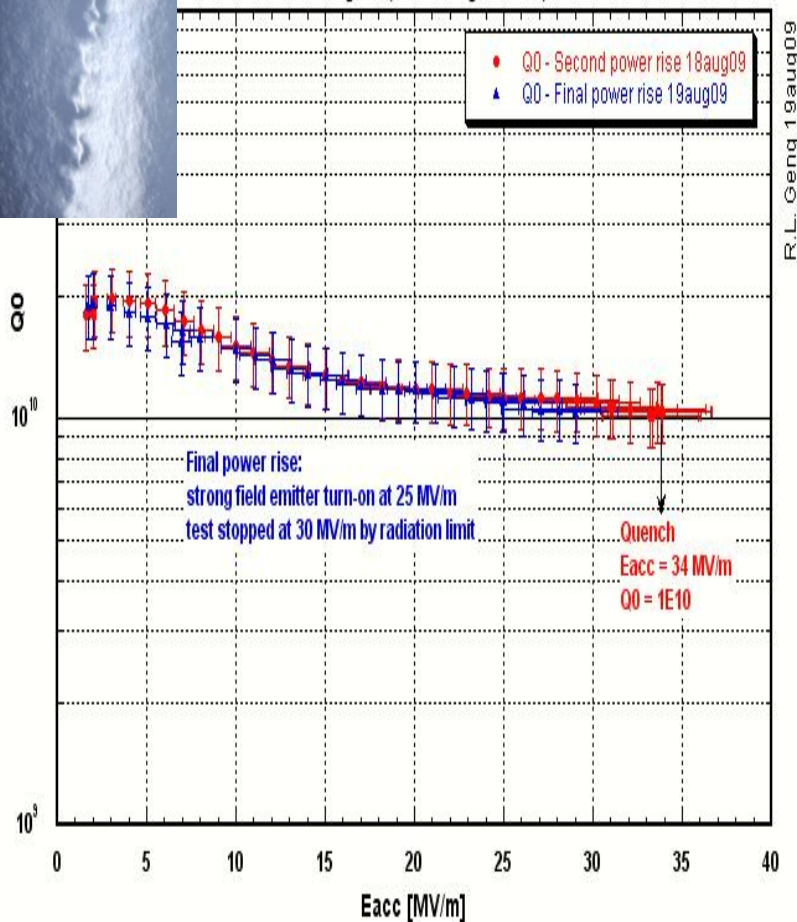
Goal: To remove surface damage created by FE during 1st-pass test

Action: EP (10+10 μm) + HPR + 120cx48hr

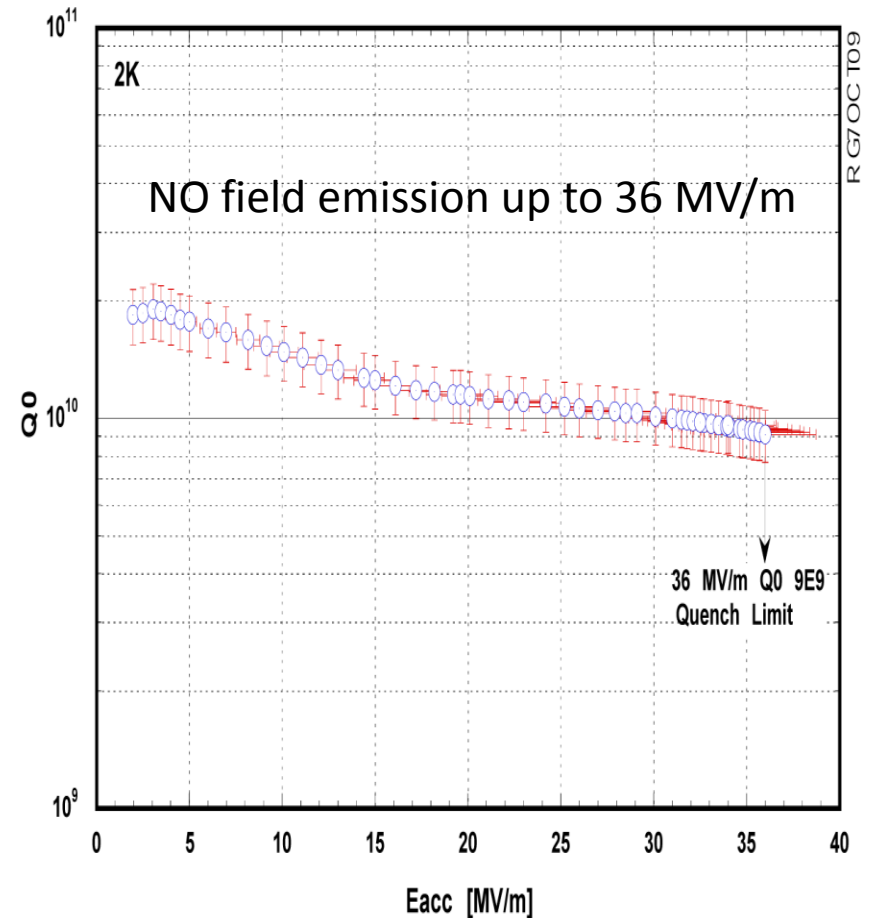
Result: Successful FE removal and raising quench gradient to 36 MV/m



AES9 after first light EP, RF test August 18-19, 2009



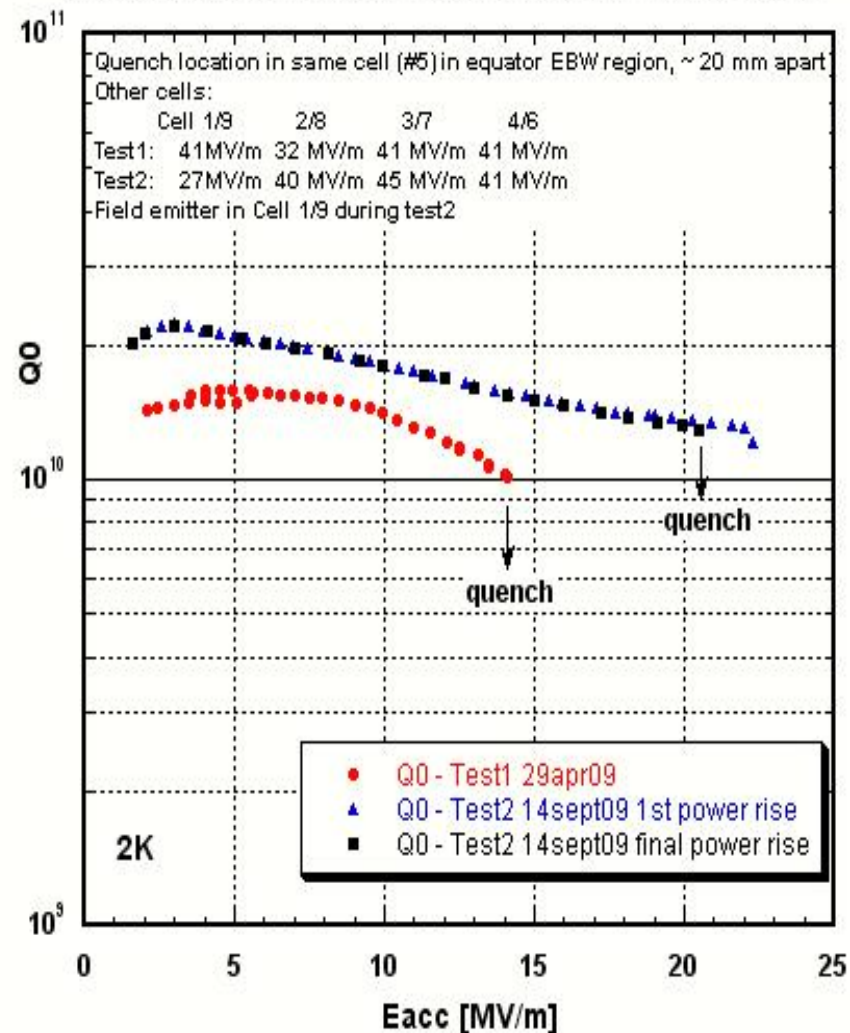
AES9 2nd-pass Qualification Performance



AES6 Second-Pass Processing

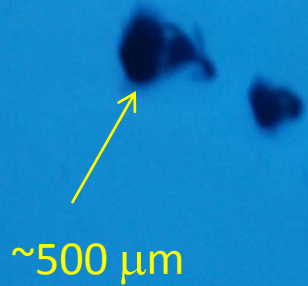
- 1st-pass test 14 MV/m.
- Quench limit.
- One defect in cell#5 (outside equator EBW).
- 2nd-pass processing:
 - Goal: check 800Cx2hr effect.
 - Action: 800Cx2hr + EP 25 um + 120Cx48hr.
 - Result: quench limit raised to 20-22 MV/m.
 - Quench limit still in cell#5, but moved to a new location, 20 mm from previous quench location and in EBW (photo later).

AES6 1st test after standard processing
and 2nd test after + 800Cx2hr + EP 25 um + 120Cx48hr



Before

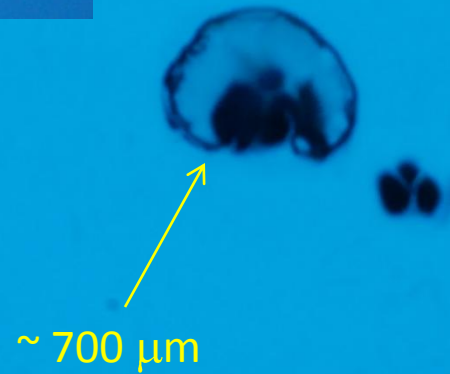
Quench limit 14 MV/m



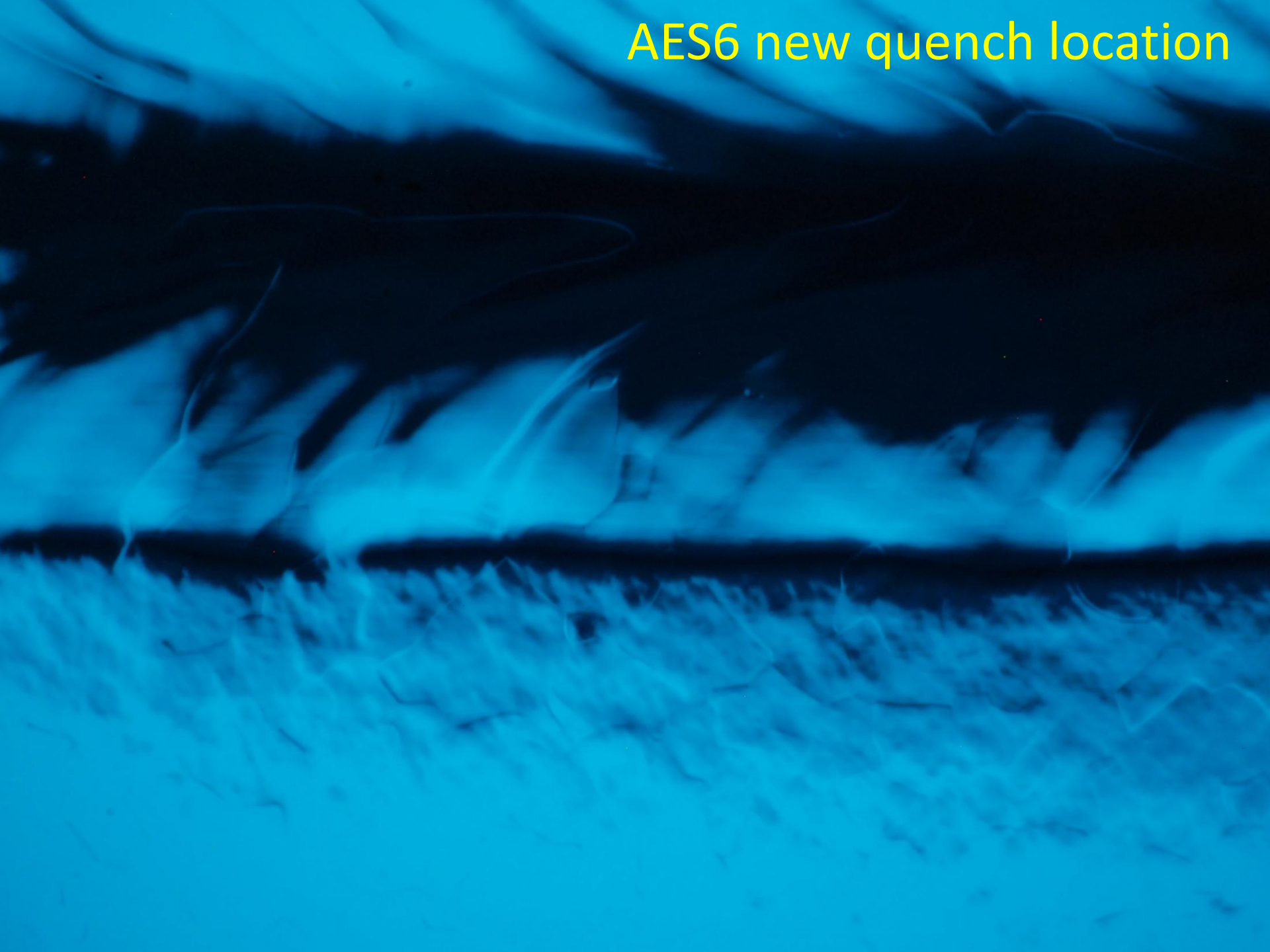
After

+800Cx2hr+EP 25 μm

Not quenching up to 22 MV/m



AES6 new quench location



Summary

- Effectiveness of data-driven 2-pass processing further validated.
- A new example of 9-cell cavity reaching > 35 MV/m without field emission.
- 2nd-pass processing of AES6 by 800Cx2hr seems to support the ideas of
 - Quench delay by improved thermal property.
 - Local suppression of RF critical field may be an operating mechanism and Magnetic field enhancement alone is not enough to explain all observed facts.
 - Independent new result of a local re-melted 1-cell cavity.